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U.S. PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date (if appropriate)
<i>MLP</i>	5 1 4 7 8 2 6	09/15/92	Liu et al.			
<i>MLP</i>	5 2 7 5 8 5 1	01/04/94	Fonash et al.			

FOREIGN PATENT DOCUMENTS

Document Number	Date	Country	Class	Subclass	Translation Yes No

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

<i>MLP</i>	C. Hayzelden et al., "In Situ Transmission Electron Microscopy Studies of Silicide-Mediated Crystallization of Amorphous Silicon" (3 pages) <i>no date or publication source</i>
<i>I</i>	A.V. Dvurechenskii et al., "Transport Phenomena in Amorphous Silicon Doped by Ion Implantation of 3d Metals" (Akademik Lavrentev Prospekt 13, 630090 Novosibirsk 90, USSR) pp. 635-640. <i>Phys. Stat. Sol. (a) 95, (1986)</i> <i>(no month)</i>
	T. Hempel et al., "Needle-Like Crystallization of Ni Doped Amorphous Silicon Thin Films", <i>Solid State Communications</i> , Vol. 85, No. 11, pp. 921-924, 1993. <i>March</i>
	R. Kakkad et al., "Crystallized Si films by low-temperature rapid thermal annealing of amorphous silicon," <i>J. Appl. Phys.</i> , 65(5), March 1, 1989, pp. 2069-72.
	G. Liu et al., "Polycrystalline silicon thin film transistors on Corning 7059 glass substrates using short time, low-temperature processing," <i>Appl. Phys. Lett.</i> 62(20), May 17, 1993, pp. 2554-2556.
	G. Liu et al., "Selective area crystallization of amorphous silicon films by low-temperature rapid thermal annealing," <i>Appl. Phys. Lett.</i> 55(7), August 14, 1989, pp. 660-662.
<i>MLP</i>	R. Kakkad et al., "Low Temperature Selective Crystallization of Amorphous Silicon," <i>Journal of Non-Crystalline Solids</i> , 115, 1989, pp. 66-68. <i>(no month)</i>

Examiner *MLP*Date Considered *1/6/96*

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.